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Action in Support of the Federal Authority's Strategic Priorities

Science Metrology for Micro and Nanotechnologies

Final Report

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Applicable Documents

[AD1]Contrat de recherche N° AP2/M01[AD2]Annexe 1 au Contrat de recherche N° AP2/M01

Reference documents

[RD1]	AP2/M01 Initial report	060621_Nanometrology_Initial Report
[RD2]	RP-CSL-NAM-06001	060621_Nanometrology_Initial Report FR

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[RD3]	RP-CSL-NAM-06002 060821 Follow-up board Report
[RD4]	MT/CSL/NAM/06001 Initial follow-on board meeting
[RD5]	MT/CSL/NAM/06002 Minutes of meeting at LNE
[RD6]	T.Dziomba, L. Koenders, G. Wilkening, Standardisation in dimensional nanometrology:
	development of a calibration guideline for Scanning Probe Microscopy. Optical fabrication
	testing and metrology II SPIE Vol 5965 JENA 2005 Germany
[RD7]	L Koenders et al, Comparison on step height measurements in the nano and micrometre
	range by scanning force microscopes Metrologia 43 04001 2006
[RD8]	K Doytchinov et al, International comparison of surface roughness and step height (depth)
	<i>standards, SIML-S2 (SIM 4.8)</i> Metrologia 43 04002 2006
[RD9]	Blind, Knut; Gauch, Stephan: Frictions in the Interface between Nanotechnology
	Research and Standardisation in Germany. Explanations and Solutions. In: Coenen,
	Heide; Gröhndahl, Jörg; Jakobs, Kai (Eds.): Standardisation and Networks. Proceedings:
	of 11th EURAS Workshop on Standardisation. Hamburg, 8-9 June. Aachen:
	Wissenschaftsverlag Mainz in Aachen, 2006, S. 61-70 (Aachener Beiträge zur Informatik
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[RD10]	Nanometrology Eighth nanoforum Report July 2006
[RD11]	Nanoscale Calibration Standards and Methods: Dimensional and Related Measurements
2 5	in the Micro- and Nanometer Range Günter Wilkening, Ludger Koenders Wiley-VCH
	Veerlag GmbH 2005
1210121	European Survey on Success Eactors, barriers and Needs for the Industrial Lintake of

[*RD12*] European Survey on Success Factors, barriers and Needs for the Industrial Uptake of Nonmaterials in SMEs, CEE Nanoraod SME report 2005



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1. Scope

This report presents the output of the study about the Belgian needs and status on nanometrology. It presents the study approach, the questionnaire used, the list of companies contacted, an analysis of the query and conclusions.

2. Introduction

The nanometrology marketplace is fully dependent on the gauges development. These later unambiguously define the technical terminology and also test procedures to determine sample characteristics.

It is of major importance to connect the standardization and research to make our companies competitive and at the top of the technology by interconnecting research centers and department in that field.

The project aims to establish an overview of nano metrology in Belgium, pointing out the techniques used by our companies, research centers and universities in this field. This work was achieved through information enquiry at the identified entities. This way gives indications of the demand in term of instrumental gauging. Survey is one possibility that has been proposed to determine the future needs of standard for the service sector.

In parallel, a study of the international state-of-the-art in the domain through an exhaustive bibliographic research (ISO and other standards, scientific journals, documents made available by foreign bureau of standards or other international organizations) was performed. However, this part is already well known at the SPF Economie (see [RD4]), but a summary is anyway provided hereafter.

3. International state of the art

3.1. Fields of nanometrology and used instruments

A general summary on application in nanotechnology can be found on <u>http://cordis.europa.eu/nanotechnology/src/pressroom_films.htm</u>, "Nanotechnology: Innovation for tomorrow's world"

It is well known that these technologies cover a wide field of applications (e.g. Optic, Integrated optics, Lithography, MOEMS, MEMS, Electronics, Coating, Powder, Biology, Precision engineering, Semiconductor, Material science, Crystallography, Chemistry, Life science, Nano engineering)

This study will be limited to Belgian applications.

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3.2. Standardisation in nanometrology

[RD6] indicates that hardware transfers are already commercially available. However there is no general accepted procedure how to perform SPM calibration. VDI/VDE – GMA 3.41/3.43 and ISO are discussing guidelines procedures on these aspects.

SPMet European Network on the calibration of SPMs took an important part in the SPM calibration procedures within EC for precision engineering.

Through EUROMET a lot of round robins are performed. One [RD7] shows that step height measurements with SPM are in good agreement with the reference values. This implies that SPM measurements are reliable and suitable for traceable measurements of step heights. The study shows that today step heights on samples can be measured with uncertainties in the sub-nanometre range.

Between 1999 and 2002, several round robin were performed (NANO2 (step height), NANO3 (Line scale), NANO4 (1D grating). They were quite successful either the instruments were quite new. Another international comparison of surface roughness and step height (depth) standards has been performed [RD8] and points out that the laboratories agree on all of the measurements within their stated and published uncertainties.

However a lot of other types of instruments are also used (see equipment list proposed in the questionnaire). Some of them use laser light, and the laser wavelength act as a "standard". These lasers are generally not stabilized. It is probably one of the reasons why nanometrology at the BIPM has been transferred to Time, Frequency and Gravimetry department.

The ISO-TC Training Committee 201 "Surface Chemical Analysis" standard is mainly driven for SPM applications in the field of chemistry, life science and crystallography.

ISO – TC229 (Initiated in May 2005 with a first meeting in November 2005 and the second June 2006). This group plan to initiate international standardization activities with the goal of contributing to facilitating nanotechnology development and utilization, as well as improving public understanding. It also decided to establish working groups (WGs) covering the three areas of 1) terminology and nomenclature; 2) measurement and characterization (including calibration and certification); and 3) health, safety and the environment. Up to now, no ISO standards have been published from this TC. The IBN (Institut Belge de Normalisation) is involved in this TC.

ANSI Nanotechnology Steering Panel attempts to cover nanotechnology standardization as a whole.

ASTM E56 Committee on Nanotechnology started also in 2005. This Committee addresses issues related to standards and guidance materials for nanotechnology & nanomaterials, as well as the coordination of existing ASTM standardization related to nanotechnology needs. This coordination includes the apportioning of specific requests for nanotechnology standards through ASTM's existing committee base, as well as the maintenance of appropriate global liaison relationships with activities (internal and external) related to this

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subject area. There are 6 working groups, one also on nomenclature, the other addresses more nanoparticule issues and carbone nanotubes.

Pr. Massalar member of the follow-on board is representative for central Europe of NSCL (National Conference of Standards Laboratories) and is member of IMEKO (International Measurement Confederation). NCSL and IMEKO are also concerned by nano metrology standards.

Finally, an entire book dedicated to nanoscale Calibration standard has been recently edited [RD11]. Since the authors are German, the book discusses mostly development and activities performed at the PTB. This book indicates that there is no standard process for microroughness and three dimensional surfaces measuring, and that there are generally no accepted guide lines. Optical and lithography techniques allows to manufacture grating down to 300 nm. It demonstrated that the topic is complex and confirms our first statement of this paragraph.

3.3. Activities in our neighbor countries and in the EC

Since the beginning of 2000, it appears obvious for several neighbor countries and at EC level that there is a need in nanotechnology to write standards, to define scientific instrumentation for measurement, to validate measurement procedures and to measure standards. EC starts a study in 2001 (EUROMET project). In GB this type of activities have also been proposed in 2002 with programs covering 2003 - 2005 (theme 4 of Science and technology in length metrology). In France, the nanometrology project starts in 1999 - 2000 under the demand of electronic industries.

Recently, final versions of the roadmap reports of NanoroadSME and NanoRoadMap were available. Both have elaborated roadmaps in the fields of energy, health and materials, the first with a focus on SMEs.

The roadmaps of **Nanoroad SME** (<u>www.nanoroad.net</u>) are as follows:

- Nanoroadmap Medical and Health (<u>http://www.nanoroad.net/download/roadmap_mh.pdf</u>)

- Nanoroadmap Energy (http://www.nanoroad.net/download/roadmap_e.pdf)

- Nanoroadmap Automotive Industry (http://www.nanoroad.net/download/roadmap_ai.pdf)

- Nanoroadmap Aeronautics Industry (http://www.nanoroad.net/download/roadmap_as.pdf)

SME surveys and SWOT analyses for these four areas have been done and can be downloaded from <u>http://www.nanoroad.net/index.php?topic=download</u>.

The roadmap reports of NanoRoadMap (<u>www.nanoroadmap.it</u>) are the following ones:

- 4 Materials roadmap reports (* Nanoporous * Nanoparticles/Nanocomposites * Dendrimers * Thin film & coatings).

- 4 Health and Medical Systems roadmap reports (* Drug encapsulation / Drug delivery / Drug targeting * Molecular Imaging / Biophotonics / Medical Imaging * Biochips / High-throughput screening / Lab-on-a-chip devices * Biomolecular sensors).

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- 4 Energy roadmap reports (* Solar cells * Thermoelectricity * Rechargeable batteries and Supercapacitors * Heat insulation and conductance).

They can be downloaded in the section reports on the <u>www.nanoroadmap.it</u> homepage.

3.4. Conclusions

Since July 2006 a report on Nanometrololy is available on the web and gives a good overview of international state-of-the-art in nanometrology.

The main highlights are:

- There is only one Belgium company pointed out working in nanometrology, while countries like The Netherlands, Danemark, Czeck Republic, Switzerland have several companies. The origin of the authors (NL, Cz) biased probably this list in someway. (pg20). It has to be noted that this Belgium Company was not aware of this.
- 2. They propose 6 categories for classifying nanostructures according dimensionality (pg 13)
 - 0 D: Nanoparticules
 - 1 D: Nanowires
 - 2 D: Coating and surface layer
 - 3 D: Bulk
 - Powders

Other Nanostructures

- 3. The overview of nanometrology initiatives (pg 17) are the one we already rise up in § 3.2.
- 4. Papers dedicated to nanometrology comprise about 7% of all the nanotechnology papers in the last 10 years. But nanotechnology is implied in a lot of areas, and nanometrology is indirectly present in nanotechnology papers. So we wouldn't take this as a negative point.
- 5. The report gives also a good overview and summary of the techniques used in nanometrology, however the selected methods are bias by the expertise of the authors.

Anyway, this interesting report can be downloaded from <u>http://www.nanoforum.org/</u> in publication heading.

Miss U. Dobre member of the follow-on board indicates that at the SPF Economie they have large international collaboration and by this way have a good knowledge of the international status on nanometrology standard. It is accepted that it is not relevant to go in deeper analysis about this topic.



From informal discussions the Table 1 of the nanometrology report is also valuable for Belgium partner where the interest in nano metrology is different between Research oriented and industrial players.

Nanometrology			
Research-oriented	Industrial		
Requires highest precision possible	Requires highest effectiveness of measuring systems		
Vision driven observations mostly	Quantitative parameters need to be measured		
Quantity of measured parameters –	Quantity of measured parameters – minimum acceptable		
as many as possible			
Measurement time and cost – are	Measurement time and cost - minimum		
not important			
Significant importance of ambient	Measurement under conditions in a production process		
conditions	(rough conditions, affected by vibration, air pollution,		
	etc.)		

Table 1

4. Questionnaire

To scan the needs of the Belgium actors in the field of nanotechnology a questionnaire was set up. It has been discussed during the initial meeting [RD4] and updated. It is presented in annex 1.

The goal was to:

- 1) point out the most used instruments in the nanotechnology field,
- 2) verify if the users are concerned by the traceability of their measurements,
- 3) consider the financial impact of wrong measurements,
- 4) evaluate further needs in nanometrology.

To avoid that people spend too much time to fill the questionnaire in, the questionnaire was simplified as much as possible and addressed mainly the instruments that the users most handle.

5. Contacted companies

First of all, we cannot be sure that all the Belgium actors involved in nanotechnology have been contacted.

The way the companies were found was through workshops (e.g. Hainova symposium in Charleroi), web search, EU web information, and CSL contacts.

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About 100 actors have been identified. Several were eliminated since they seemed not really concerned by measurements as user e.g. modeling lab, simulation, doubloons,..., or because they are not really implicated in nanotechnology.

After this first selection, about 50 players remain and were contacted by email, 50% replies and 40% fill actually the questionnaire. In total our analysis is based on 18 answers by researchers and responsibles in the field. The name of the contacted company, their coordinates and their fields of activities are presented in annex 2. It has to be noticed that some companies at first view which shall be concerned by nanometrology and standard didn't reply. Oral contacts were also performed to work out some of the points addressed in the questionnaire.



Fig 1 : Replies success

It is estimated that the sampling is large enough to provide a general overview of the nanometrology users in Belgium. The result is not so bad, compared to similar study in Germany [RD9] or at EC. In Germany a response rate of 28% was achieved. A total number of 65 questionnaires were filled. Half of the questionnaires were collected during two national conferences, opportunity that we didn't have in Belgium. Additionally, it is well known that Germany occupies a leading position in the field. At EC, 19% of replies were collected for the SME survey <u>http://www.nanoroad.net/index.php?topic=download</u>.

6. Questionnaire replies

6.1. Flemish/Wallonia-Brussels parity

The query is well balance between Flemish and Wallonia. The Large companies are not taken into account in this rating. The actual ratio was Flemish/Wallonia-Brussels = 82%. This does not indicate that the nanotechnology is more developed in Wallonia. A larger reply rate was encountered in the Flemish region while more entities were contacted in the Wallonia-Brussels region.





Fig 2 : Ratio between Flemish and Wallonia replies

6.2. General information about participants

It was easier to find university and research center actors in the field of nanotechnology than industries. University services working in nanotechnologies are well identified (e.g. Nanowal web site). Since the field is new, it is not a surprise that universities look like the most involved in the field. For large companies, their core business is hiding their nanotechnology business.

The sharing between the repliers is represented in the figure hereunder.



Fig 3 : Replier profile

6.3. Most addressed field

The addressed fields are rated hereafter.

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Optics	16 %	Precision engineering	5 %
Electronics	16 %	Material science	81 %
Biology / Life science	31 %	Chemistry	62 %

The sum of the percents is higher than 100 %, since several fields are addressed simultaneously by some of the entities. Material science is the topics the most studied in nanotechnology. The same is observed in EC studies (e.g. [RD12]). This can be understood since it is the fundamental of all the applications. However chemistry takes also a good place in the field. Large companies are also concerned by material science. No replies were received from nanobiology industries that are probably not concerned by dimensional metrology.

6.4. Materials, components most studied or measured

This question was related to the materials most used. The replies didn't indicate precisely a chemical composition but generally a chemical group. The replies have been arranged by type of activities.

Coating activity

Polymer coatings, inorganic coatings, organic molecules (self-assembled monolayers), low k materials,... organic coatings with nano-particles included, fillers in polymers, metallic oxide coatings, optical thin films (like, e.g., diamond like carbon coatings), thin films of metals.

Micro-nanoelectronic

MicroElectroMechanical Systems (MEMS). Nanoscale transistors as well as NanoElectroMechanical Systems (NEMS). Analyze the doping atoms distribution in thin silicon layers after activation. Ceramic superconductors, photovoltaics.

Materials

Nanomaterials (like, e.g., nanoparticles of transition and rare earth metal oxides, nanotubes(CNT)), alloys) nanostructured oxide materials (like, e.g., STO- LAO multilayers), pervoskite based materials, alloys (like, e.g., Ni-Ti shape memory) Conductive polymers, diamond, oxide nanoparticles silicon nanowires, carbon nanotubes, III-V material nanowires Aluminium alloys and ceramics.

<u>Chemical</u>

Catalysts (heterogeneous and homogeneous), zeolites, CdS-nanocolloids. Particles, metals and oxides, ceramics, nitrides and carbides, DLC (including films containing nanoprecipitates) Thermoplastic polymers, Composites (thermoplastics and thermosets) Nanocomposites (TP/TD polymers + CNT, nanoclays),), Polymers (PVC, PVDC, PVDF, PA, PSu, etc.), catalysts, chemicals, additives (fillers, pigments, etc.)

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Biology/life science

Proteins, DNA, dendrimers, aromatic molecules, etc. Templates for the growth of Cnanotubes, biosensors, microelectronic structures, material from third companies lipidlayers, nanovesicles (triblock polymers), proteins, protein crystals, DNA (plasmids, short strands), colloïds pharmaceuticals, polymers, proteins/peptides

Powders

Powders of metals. Nanopowders (carbides, nitrides, oxides and pure metals nanopowders)

6.5. Available and most used instrumentations

The next question is related to the tools and methods used in Belgium nanotechnology business.

The 3 most used instruments are in red, the next 3 in blue. A summary description of these devices can be found in [RD10].

	Available on site	Most used within the companies
Atomic Force Microscopy (AFM) or Scanning Force Microscopy (SFM)	11/18	8/18
Electron Diffraction (ED)	8/18	0/18
Scanning Tunnelling Microscopy (STM)	5/18	1/18
Scanning Electron Microscopy (SEM)	15/18	11/18
Transmission Electron Microscopy (TEM)	11/18	4/18
Scanning Transmission Electron Microscopy (STEM)	6/18	2/18
Small Angle Neutron Scattering (SANS)	0/18	0/18
Small Angle XRay Scattering (SAXS)	2/18	0/18
Scanning Near-field Optical Microscopy (SNOM or NSOM)	1/18	0/18
Electron Energy Loss Spectroscopy (EELS)	4/18	0/18
Energy Dispersive X-Ray Spectroscopy (EDX or EDS or XEDS)	9/18	6/18
X-Ray Diffraction (XRD)	10/18	4/18
X-Ray Absorption Spectroscopy (XAS)	0/18	0/18
Neutron Diffraction (ND)	0/18	0/18
Single Molecule Spectroscopy (SMS)	2/18	0/18
Auger Electron Spectroscopy (AES)	3/18	0/18

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Polarization Spectroscopy (PS)	1/18	0/18
PhotoluminescenceSpectrocopy(PL),ElectroluminescenceSpectroscopy(EL),CathodoluminescenceSpectroscopy (CL)	2/18	0/18
Fourier Transform Infrared Spectroscopy (FTIR)	7/18	4/18
Raman Spectroscopy (RS)	6/18	4/18
X-Ray Photoelectron Spectroscopy (XPS) or Electron Spectroscopy For Chemical Analysis (ESCA)	2/18	0/18
Profilometer (PROF)	6/18	1/18
Secondary Ion Mass Spectrometry (SIMS)	2/18	0/18
Differential Scanning Calorimetry (DSC)	10/18	0/18
Mössbauer Spectroscopy (MS)	0/18	0/18
Nuclear Magnetic Resonance (NMR)	6/18	2/18
Cyclic Voltammetry (CV) and Linear Sweep Voltammetry (LSV)	4/18	0/18
Four point probe AND I-V techniques (4P)	4/18	0/18
Capacitance spectroscopy (CS)	1/18	0/18
Other : Interferometer	2/18	1/18

The table indicates that the Belgium labs are well equipped; it is possible to find nearly all types of instruments listed and additional ones that were not in the initial questionnaire. A description of most of the instruments can be found in [RD10].

SEM is available in 84% of the labs. It is also the instrument the most used. The next one is the AFM, followed by EDT.

6.6. Instrumentation environment

This question is related to the environmental conditions of the lab where the instruments are located. This is connected to the uncertainty of the measurement.

Standard lab	50 %
Clean room	37 %
Lab + Air Condition	68 %
Damping	36 %
Pressure	0 %

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Most of the users work in a temperature controlled lab. The temperature control is usually +/-1°C or better. When damping is present, it is always on a dumping system provided with the metrology instrument, and not a damped floor. Some users work in clean rooms but the latter are not always classified.

6.7. Range and incertitude

These questions are related to the performances achieved or at least announced within the classical measurement procedures. It concerns also if relative or absolute measurements are needed. Finally, the question tackles if the users are satisfied with the measurement uncertainty.

In which range do you measure (x nm to y μ m)?	few nm to few 100 µm
With which uncertainty	0.1 nm to 20 %
If not sufficient, what uncertainty would you need?	Most of the answers show that the users are happy with what they have.
Absolute / relative measurements	10 absolute, 5 relative, 3 both

The range is quite large, and the uncertainty mostly depends on the instruments used. The announced uncertainties (e.g. 0.1 nm) are indications coming from the instrument manufacturer. The question indicates that there is no need for better measurements. Additionally, there is no guarantee that the question is well understood. Most people are not necessarily specialized in measurement techniques, and there is a potential mismatch between the terminologies used (e.g. uncertainty, accuracy, resolution, repeatability, absolute error ...). Most of the users ask for absolute measurement, but without any care to traceability to a standard as it can be understood from the next questions.

6.8. Standard and procedure

This part tries to understand with which guarantees the previous figures are achieved.

Do you use special measurement protocols? If yes, which one (ISO, In home,)	66% have no special protocol. The remaining ones use internal procedures. These are based on the user manual of the instrument provider.
Are you concerned only by the functionalities of the components you develop or is it required that this product is further interfaced or in interaction with a	The replies are not obvious. Nevertheless the next question indicates that interface problem do not occur frequently.



third party hardware?	
When it is required to have compatibility, how do you fix the rules?	Usually not required.
How do you ensure consistent measurements, and how do you know the part meets the specification?	Check consistency wrt other instruments, or well known pieces reference hardware or physical properties
What type of terminology do you use (scientific, commercial, in home, standard)?	All the users employ scientific terminology
Do you need accredited measurements?	Nobody needs accreditation

Most of the users declare explicitly to not use special measurement protocols. The remaining ones use internal procedures inspire from the instrument procedures, their knowledge of their tested items and code of best practice. There is no particular demand for protocol except only one for sample preparation.

The interface aspects are not critical; this sector in Belgium is not mature enough for large hardware exchange between laboratories and/or industries. When interface problems occur they are handled through test plans.

To improve the confidence in the measurement, the approach is to cross-correlate measurements with different instruments. Most of the labs having several instruments are able to do this internally. Another way to evaluate the instrument is to use known physical parameters. Only one lab indicates participating to round robin.

The terminology used is scientific, the one codified trough scientific publication. Presently, nobody required accreditation, labs have no money for it, it just can give an added value.

6.9. Measurement and calibration frequency

These questions concern the calibration process used related to the used frequency

How frequently do you measure (n°/week)?	More than 1/day with the most frequent instrument to 1/week with the other
How frequently do you perform the maintenance of the instrument (n°/year)?	At least 1/year.
How frequently do you perform a recalibration of the instrument (n°/year)?	Most 1/year
What procedure is followed for the	The calibration is generally done in

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calibration?	home with manufacturer procedure and staff. Return to the manufacturer is exceptional.
What is the calibration process you use? E.g.: gauge blocks, which references, which material	Calibration grids are used

The nanometrology tools are used quite frequently. This indicates that the instrument operators have a good follow on and good understanding of the instruments. This provides additional confidence in the measurements.

Concerning the maintenance and calibration issues, these are performed once a year as advised by the manufacturers. Or even more for some instruments more sensitive to ageing effect or more frequently used.

Almost all the consulted people use calibrated grids. These are not well identified but are advised by the manufacturer. Some labs have dedicated sample for these calibration activities.

6.10. Cost impact

This question is related to the cost impact of wrong measurements.

What is the cost impact of wrong measurements	Variable	
that is the cost impact of mong measurements	(anabio	

It is a point that it is difficult to evaluate. In universities the impact is mostly bad science and a loss of time. In industries, it starts from a waste of time to several 10 000 of Euros and can be really catastrophic in SME.

The reason why cost impact evaluation is difficult is that this evaluation depends on several parameters. Example of sub cost impacts are:

- Cost to redo the measurement
- Cost to redo the hardware
- Cost to improve or correct the system
- Cost link to discarding a good device
- Juridical cost
- Lost in reputation \rightarrow lost of potential customer

From this list of parameters it is obvious that it not always easy to provide accurate figures, knowing that these cost impact factors are also depending on the component or process involved.

Another aspect linked particularly to the nano field, is that the dimension of nano materials and nano particles is lower than the standard physical phenomenon size characteristics and by this way several physical, optical or chemical properties start to become completely different.

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During the process, dimensional measurements are taken, but at the end only the final functionalities are considered. This method gives warranties again the measurement error. For this, the cost impact is only limited to hardware and the operation between the dimensional and the expected functionalities measurements.

6.11. Further needs

Final questions try to evaluate the actual and further needs in nanometrology and the opted solution when the metrology tools are not available.

When you need accurate measurements that are not available at your premises, how do you proceed?	All the users ask to another well known lab
Do you have or see other concerns or demands for nanometrology for your current or future activities?	Quantification of size and shape of nanoparticles
	Sample preparation
	Safety is currently a big concern with nanomaterials such as carbon nanotubes, nanowires and nanoparticles. Special precautions have already been taken for working with carbon nanotubes and their shipment.
	Profilometry

When the measurement instrument is not available on site, the user goes to another well known laboratory. However, this procedure is quite less frequent than several years ago. Now, it is not more exceptional to have a SEM in a small lab. Additionally, the dedicated instrument needed for their daily applications is also available in home. In SME or start up, where these instruments are too costly, they have a network of companies able to perform the measurements.

The further needs are quite low and some already taken in consideration in actual international developments.

Safety is currently a big concern with nanomaterials and is considered in the Nanosafe EC project.

For sample preparation, an ISO platform is taking care to establish well accepted procedures in sample preparation.

Profilometry. A lot of commercial profilometers (Veeco Dektak, nanosurf, FRT GmH, ...) and in home profilometers (CSL, TNO, NPL, PTB, LNE) are becoming available. However, care

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must be taken in the understanding of the performances (e.g. repeatability of 1 nm is repeatability when there is no displacement of the probe, which is no what a profilometer users want (repeatability over a scan)). The same is true for quantification of size and shape of nanoparticles, where several techniques as laser granulometry are commercially available.

7. Conclusion

The enquiry indicates that in Belgium

- it is possible to find all types of instruments used in nanotechnology,
- the organizations concerned by nanotechnology work mostly with Scanning Electron Microscope (SEM) instruments, while in Germany SPM looks to be the most used [RD6]. SEM are available in 85% of the consulted labs. SEM are generally used for topographic measurements,
- none of entities required accreditation,
- when calibrations are performed, calibrated grids are employed. The calibration process generally accepted used VLSI grids (<u>http://www.vlsistandards.com/home/default.asp</u>),
- the instruments are generally located in a standard lab with controlled temperature, only 20% are in clean room,
- when the measurement facility is not available on site, well know labs are addressed,
- the parity between Wallonia and Flemish is well balanced but there is no indication that a region is more involved than another,
- 45 % of actors are universities. It was easier to find university actors in the field of nanotechnology than industries. Additionally, this activities is quite new and concern most research activities than industrial production,
- material science is the topics the most studied in nanotechnology,
- the measurement range is quite large between 1 nm up to 100 μm, as well as the uncertainty 0.1 nm to 20%. These are linked to the applications. The users are more concerned by absolute measurements than relative,
- the instruments are well used generally more than once a day. The calibration and maintenance are performed once a year at the user premises with the help of the instrument manufacturer staff,
- the cost impact of wrong measurements is quite variable, from bad science in university and waste of time to several 10 k€ in industry. The standard way to minimize this is to check consistency with respect to other instruments,
- the particular additional demands for future activity highlighted are already covered by international activities.



- A similar study is performed in France by the LNE. It has been proposed to compare the results.

8. Acknowledgements

We thank all the contributors that kindly replied to the questionnaire.

9. Annex 1 : Questionnaire

The concern is to know if precise control of dimensions of object (3D, layer, powder ...) is a key issue in nanotechnology.

The goals of the questionnaire are :

- 1) To evaluate the most used instruments and methods in nanometrology by the Belgium nanotechnology community.
- 2) To evaluate how standard and interface are handled and needed by the Belgium nanotechnology community.

9.1. General questions on your core business in nanotechnology

Name of the company:

Name of the department:

SME : University: Large company: Research center:

Field of activity:

Optics	
Electronics	
Biology / Life science	
Precision engineering	
Material science	
Chemistry	
Other please specify	



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9.2. Dedicated questions on your dimensional metrology activity

1	What are the materials, components you most study or measure?		
	Chemical name, type of polymers, type of powder, coating material,(e.g: CdSe/ZnS core shell nanocrystal, PbTe nanorods,)		
2	What types of instruments are available in	Atomic Force Microscopy(AFM) or Scanning Force Microscopy(SFM)	
	your company (put a cross in the last	Electron Diffraction (ED)	
	column when available at your premises).	Scanning Tunneling Microscopy (STM)	
	, , , , , , , , , , , , , , , , , , ,	Scanning Electron Microscopy (SEM)	
		Transmission Electron Microscopy (TEM)	
		Scanning Transmission Electron Microscopy (STEM)	
		Small Angle Neutron Scattering (SANS)	
		Small Angle XRay Scattering (SAXS)	
		Scanning Near-field Optical Microscopy (SNOM or NSOM)	
		Electron Energy Loss Spectroscopy (EELS)	
		Energy Dispersive XRay	
		spectroscopy(EDX or EDS or XEDS)	
		X-Ray Diffraction (XRD)	
		X-Ray Absorption Spectroscopy (XAS)	
		Neutron Diffraction (ND)	
	Other? Please fill here below	Singlemolecule spectroscopy (SMS)	
		Auger Electron Spectroscopy (AES)	
		Polarization Spectroscopy (PS)	
		Floctroluminescence Spectroscopy (PL),	
		(FL) Cathodoluminescence	
		Spectroscopy(CL)	
		Fourier Transform Infrared	
		Spectroscopy (FTIR)	
		Raman Spectroscopy (RS)	
		X-Ray Photoelectron Spectroscopy	
		(XPS) or Electron Spectroscopy For	
		Chemical Analysis (ESCA)	
		Profilometer (PROF)	
		Secondary Ion Mass Spectrometry (SIMS)	
		Differential Scanning Calorimetry (DSC)	
		Mössbauer Spectroscopy (MS)	
		Nuclear Magnetic Resonance (NMR)	
		Cyclic Voltammetry (CV) and Linear	
		Sweep Voltammetry (LSV)	
		Four point probe AND I-V techniques	
		(+r) Capacitance spectroscopy (CS)	
1			



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3	With respect to the previous list, what type of instruments are you using most frequently?	
	Brand name:	
	Туре:	
4	Are there particular environmental conditions where your instrument(s) is (are)	Standard lab
	located and used?	Clean room (which class)
		Air Condition room (which temperature stability)
		Pressure
		Damping system
		Other
5	In which range do you measure (x nm to y $\mu m)?$	
6.a	With which uncertainty?	
6.b	If not sufficient, what uncertainty would you need?	
7	Do you need relative or absolute measurement? Why?	
8	Do you use special measurement protocols? If yes, which one (ISO, In home,)	
9	How frequently do you measure (n°/week)?	
10	How frequently do you perform the maintenance of the instrument (n°/year)?	
11	How frequently do you perform a	



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	recalibration of the instrument (n°/year)?	
12	What procedure is followed for the	Return to the manufacturer
	Calibration	In home with manufacturer
		In home with manufacturer procedure
		In home with self established procedure
		Other please specified
13	What is the calibration process you use?	
	E.g.: gauge blocks, which references, which material	
14	Are you concerned only by the functionalities of the components you develop or is it required that this product is further interfaced or in interaction with a third party hardware?	
15	When it is required to have compatibility, how do you fix the rules?	
16	How do you ensure consistent measurements, and how do you know the part meets the specification?	
17	What is the cost impact of wrong measurements?	
18	What type of terminology do you used (scientific, commercial, in home, standard)?	
19	When you need accurate measurements	Ask to another well know lab
	do you proceed?	Ask to an accredited lab
		It doesn't matter unless the measurements are performed

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20	Do you need accredited measurements?	
21	Do you have or see other concerns or demands for nanometrology for your current or future activities?	

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10. Annex 2: List of contacted Industries, research centers and universities

N °	Name	Contact Person	Phone/email	Type of activity	Reply
1	Agfa Gevaerts	Chris Van Roost	http://www.agfa.com/en/sp/for ms/contactus.jsp	Metrology department	OK
2	Belgian Ceramic Research Centre http://www. bcrc.be/	Fabrice Petit	j.lagneau@bcrc.be	Nano composites, new concept of standardization which allows materials to be classified on the basis of their level of performance for a given mode of stress.	NR
3	Bekaert NV	Nadine Van de Velde	bekaert.engineering@bekaert .com	Material	NR
4	Biovallee	JF Dierick	xavier.barthelemy@biovallee. be	Biology, genomic	Restructu ration phase concernin g the R&D projects
5	Centexbel		<u>philippe.vanacker@centexbel</u> . <u>be</u>	Smart Textile	NR after indicating they concern about nanometr ology
6	Certech	Henri May	info@certech.be	R&D services	OK
	CoRI	Céline, de Lame Sophie	vonckx.s@cori-coatings.be +32 2 652 22 49	Anticorrosion, Paint Formulation	NR
7	Crif	Vonckx Frederik	Umberto.baraldi@crif.be	Powder	
8		Cambier	<u>+32 498 91 93 91</u>		ок

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	CSL	Denis	dvandermael@ulg.ac.be		
9		vanderm			ОК
	Eurogentec		ph.boulton@eurogentec.com	Nanobiology	NR
1	Ű		<u>32 4 366 61 61</u>		
0					
	FLAMAC	Johan		Flanders Materials center	
1		Paul	<u>32 9 264 58 13</u>		
1		director	johan.paul@flamac.be		OK
	GIGA	Serge	pampfer.giga@ulg.ac.be	Nanobiology	Not
		Pampfer	<pampter.glga@ulg.ac.be></pampter.glga@ulg.ac.be>		concerne
1					u
2					
1	Glaverbel		DOMINIQUE.MICHIELS@gla	Glass Coating	
3		Malloliat	verbei.com		OK
1	IMOMEC	<u>M.d'Olisi</u>		Science of materials	OK
4		<u>deyei</u> Thomas	Materials & Components	Electronic	UK
		Hantsch	Analysis		
		el	Tel: +32-16-28-1056		
		Operatio	Email:		
1		nal	thomas.hantschel@imec.be		
5		Manager			OK
	LUXILON	Herbert	nico.vanmalderen@luxilon.be	High tec mono filaments	
		De	Industriepark / Vosveld 11	5	
		Breuck	B-2110 Anvers, Belgique		
			<u>tél. +32 (0)3 326 33 88</u>		
1					
6					NR
	MATERIA		michael.alexandre@umh.ac.b	Material analysis TGA-	
	NOVA		e	DTA thermogravimetry	
			<u>065/37 34 81</u>	coupled with mass	
				spectroscopy, micro and	
				spectroscopy, micro and nano-hardness, dilatometry X-Ray	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry and specific surface	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry and specific surface measurement, rheometry, ,	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry and specific surface measurement, rheometry, , , He-Ne laser	
				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry and specific surface measurement, rheometry, , , He-Ne laser ellipsometry, specific electrical	
1				spectroscopy, micro and nano-hardness, dilatometry, X-Ray diffraction and X fluorescence, LASER granulometry, porosimetry and specific surface measurement, rheometry, , , He-Ne laser ellipsometry, specific electrical charge, Langmuir-Blodgett	Wait

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				spectroscopy in XPS, Tof- SIMS spectroscopy,	
1 8	NANOCYL	<u>F. Luizi</u>		<u>C Nanotube</u>	
1 9	<u>Nanoshape</u>	<u>Marc</u> Wieland s	marc.wielandts@amos.be	Mirror manufacturing	ок
2	<u>Solvay</u>	Dr Antoine GHANE M	Phone : 32(0)2-2643422 mailto:antoine.ghanem@solv ay.com	SOLVAY Research and Technology Materials Characterization Analytical Technologies	OK
2	VITO	Frans Snijkers	Rosita Persoons Tel. + 32 14 33 57 30 rosita.persoons@vito.be		NR
	Name	Instituti on	e-mail	Type of activity	
2 2	Bayot, Vincent	UCL	bayot@dice.ucl.ac.be	Nano electronic SEMCv	NR
2 3	Beyer, Günter	Eupen AG	gbeyer@euregio.net	Nanocomposites as flame retardants for polymers	NR
2 4	Buess- Herman, Claudine	ULB	cbuess@ulb.ac.be	Tailoring of electrode surfaces Characterization of surfaces by electrochemical methods, FTIR, STM, AFM	NR
2 5	Delplancke, Jean-Luc	ULB	j <u>delpla@ulb.ac.be</u>	Metallic nanopowder production and characterization - Matter and Materials Department	at CEE DG RTE

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2 6	Delplancke, M.P.	ULB	mpdelpla@ulb.ac.be	Nanocomposite layers – Multifunctional coating	ок
2 7	Deparis, Olivier	FUNDP	odeparis@fundp.ac.be	Engineering nano- structured optical materials	NR
2 8	De Pauw, Edwin	ULg	E.DePauw@ulg.ac.be	NOMADE Nanoparticles for Optical and MAgnetic Detection	NR
2 9	Dubois, Philippe	UMH	Philippe.dubois@umh.ac.be	Preparation and characterization of polymer nanocomposites	NR
3 0	Dufrene, Yves	UCL	dufrene@cifa.ucl.ac.be	Exploring biosystems on the nanoscale : from single molecules to living cells	NR
3 1	Ferain, Etienne	UCL	ferain@poly.ucl.ac.be	Track Etching Technology OK	NR
3 2	Grandfils, Christian	ULg CATµ	C.Grandfils@ulg.ac.be	Nanoparticles for drug delivery and diagnostic OK 32 4 366 3506	ОК
3 3	Jerome, Christine	ULg	C.Jerome@ulg.ac.be	Synthesis and surface functionalization of metallic nanodots	NR
3 4	Jonas, Alain	UCL	jonas@poly.ucl.ac.be	Nanotech Research in Alain M. Jonas' Group	ок
3 5	Lazzaroni, Roberto	UMH	Roberto@averell.umh.ac.be	Peptosome-based NanostructuredNetwork	NR
3 6	Lecomte- Beckers, Jacqueline	ULg	Jacqueline.Lecomte@ulg.ac. be	Alliage de titane / nano- structuré	NR
3 7	Legras, Roger	UCL	legras@poly.ucl.ac.be	Track Etching Technology	NR
3 8	Muller, Robert	UMH	Robert.muller@umh.ac.be	development of nanomagnetic systems as contrast agents for magnetic resonance imaging (MRI),	NR
3 9	Pirard, Jean-Paul	ULg	Jean-Paul.Pirard@ulg.ac.be	Nanostructured sol-gel porous materials	NR
4 0	Piraux, Luc	UCL	piraux@pcpm.ucl.ac.be	nanoporous media and nanowire	NR
4 1	Raskin, Jean-Pierre	UCL	raskin@emic.ucl.ac.be	CERIM	ОК
4	Wautelet, Michel	UMH	michel.wautelet@umh.ac.be	Modele Unite de Photonique Experimental	

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_	Develo		Ronnie.Willaert@vub.ac.be <ronnie.willaert@vub.ac.be ></ronnie.willaert@vub.ac.be 		
4	<u>Ronnie</u> Willaert	VUB		Ultrastructure	ок
		Universit	rolf.erni@ua.ac.be		
		eit			
4		Antwerp		Electron Microscopy for	
4	Rolf Erni	en		Material Science	OK
4				Inorganic and Physical	
5		U Gent		Chemistry	OK
4	Vander				
6	Auweraer	KUL		organic molecules	OK